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(74) Agents: ELLIS, Edward, J. et al.; Darby & Darby P.C.,  
805 Third Avenue, New York, NY 10022-7513 (US).

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(71) Applicant (*for all designated States except US*): CARL  
ZEISS SEMICONDUCTOR MANUFACTURING  
TECHNOLOGIES AG [DE/DE]; 73446 Oberkochen  
(DE).

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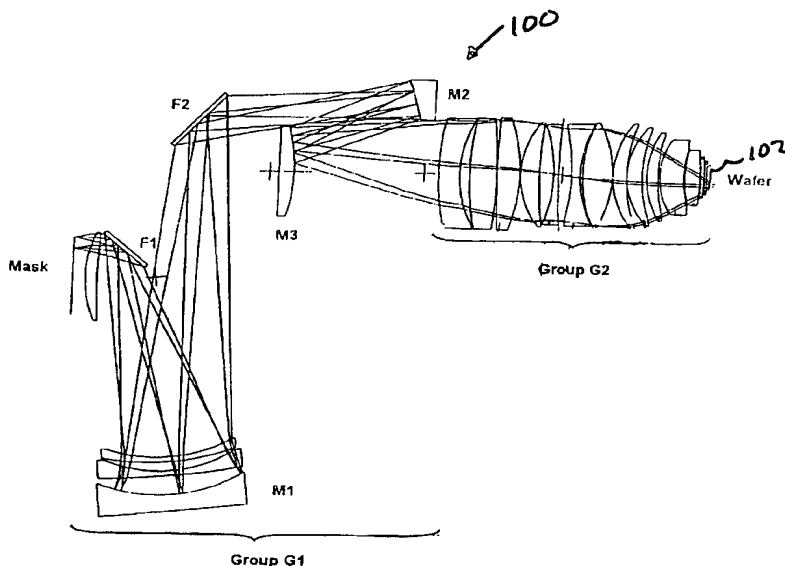
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(72) Inventors; and

(75) Inventors/Applicants (*for US only*): HUDYMA, Russell  
[US/US]; 21 Eastridge Lane, San Ramon, CA 94583 (US).  
ULRICH, Wilhelm [DE/DE]; Ledetackering 44, 73434  
Aalen (DE).

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(54) Title: CATADIOPTRIC MULTI-MIRROR SYSTEMS FOR PROTECTION LITHOGRAPHY



(57) Abstract: According to one exemplary embodiment, a photolithographic reduction projection catadioptric objective is provided and includes a first optical group (G1) and a second substantially refractive optical group (G2) more image forward than the first optical group (G1). The second optical group (G2) includes a number of lens elements (L4-L16) and has a negative overall magnifying power for providing image reduction. The first optical group (G1) has a folded geometry for producing a virtual image and the second optical group (G2) receives and reduces the virtual image to form an image with a numerical aperture of at least substantially (0.80).

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